

INTERNATIONAL SEARCH REPORT

PCT/EP2004/014290

A. CLASSIFICATION OF SUBJECT MATTER
IPC 7 G03F7/20

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)
IPC 7 G03F

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal , INSPEC, PAJ

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
Y	US 2003/174408 A1 (ROSTALSKI HANS-JUERGEN ET AL) 18 September 2003 (2003-09-18)	1-10
X	paragraphs [0025], [0036]; figure 3; table 5	13, 14
P, Y	----- JOHN H. BURNETT ET AL.: "High Index Materials for 193nm and 157nm Immersion Lithography" INTERNATIONAL SEMATECH, 2 August 2004 (2004-08-02), XP00207229 International Symposium on Immersion & 157 nm Lithography, Vancouver cited in the application the whole document	1-10
X	----- US 2002/102497 A1 (SPARROW ROBERT W) 1 August 2002 (2002-08-01) paragraph [0010] ----- Λ-	13, 14

☒ Further documents are listed in the continuation of box C.

☒ Patent family members are listed in annex.

* Special categories of cited documents :

"A" document defining the general state of the art which is not considered to be of particular relevance

"E" earlier document but published on or after the international filing date

"L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)

"O" document referring to an oral disclosure, use, exhibition or other means

"P" document published prior to the international filing date but later than the priority date claimed

"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

"Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art.

"&" document member of the same patent family

Date of the actual completion of the international search

5 August 2005

Date of mailing of the international search report

10. M05

Name and mailing address of the ISA

European Patent Office, P.B. 5818 Patentlaan 2
NL- 2280 HV Rijswijk
Tel. (+31-70) 340-2040, Tx. 31 651 epo nl,
Fax: (+31-70) 340-3016

Authorized officer

Ei sner, K

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C.(Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT

Category *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
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Y	US 4 861 148 A (SATO ET AL) 29 August 1989 (1989-08-29) column I ₅ line 59 -----	I
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Y	US 6 025 115 A (KOMATSU ET AL) 15 February 2000 (2000-02-15) column 32, line 51 -----	1
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A	EP 0 475 020 A (INTERNATIONAL BUSINESS MACHINES CORPORATION) 18 March 1992 (1992-03-18) page 4, line 57 -----	1
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INTERNATIONAL SEARCH REPORT

International application No.
PCT/EP2004/014290

Box II Observations where certain claims were found unsearchable (Continuation of item 2 of first sheet)

This International Search Report has not been established in respect of certain claims under Article 17(2)(a) for the following reasons:

1. ☐ Claims Nos.:
because they relate to subject matter not required to be searched by this Authority, namely:
2. ☐ Claims Nos.:
because they relate to parts of the International Application that do not comply with the prescribed requirements to such an extent that no meaningful International Search can be carried out, specifically:
3. ☐ Claims Nos.:
because they are dependent claims and are not drafted in accordance with the second and third sentences of Rule 6.4(a).

Box III Observations where unity of invention is lacking (Continuation of item 3 of first sheet)

This International Searching Authority found multiple inventions in this international application, as follows:

see additional sheet

1. ☐ As all required additional search fees were timely paid by the applicant, this International Search Report covers all searchable claims.
2. ☐ As all searchable claims could be searched without effort justifying an additional fee, this Authority did not invite payment of any additional fee.
3. ☐ As only some of the required additional search fees were timely paid by the applicant, this International Search Report covers only those claims for which fees were paid, specifically claims Nos.:
4. ☒ No required additional search fees were timely paid by the applicant. Consequently, this International Search Report is restricted to the invention first mentioned in the claims; it is covered by claims Nos.:
1-10, 13, 14

Remark on Protest

- ☐ The additional search fees were accompanied by the applicant's protest.
- ☐ No protest accompanied the payment of additional search fees.

FURTHER INFORMATION CONTINUED FROM PCT/ISA/ 210

This International Searching Authority found multiple (groups of) inventions in this international application, as follows:

1. claims: 1-10, 13, 14

prior art: Microlithography projection objective with a numerical aperture larger than 1 and with a lens made from different crystals

special technical feature: Microlithography projection objective with a lens of crystal materials made from NaCl, KCl, KI, NaI, RbI, CsI, MgO, MgAl₂O₄ or Y₃Al₅O₁₃.

problem solved by these technical features:

high refraction index material increases the numerical aperture of the objective

2. claims: 11, 12

special technical feature:

end plate of a microlithography projection objective made from crystalline magnesium oxide.

problem solved by these technical features:

protection plate for other optical elements

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Patent document cited in search report		Publication date	Patent family member(s)			Publication date
US 2003174408	A1	18-09-2003	AU	2002312872	A1	22-09--2003
			AU	2003221490	A1	22-09--2003
			CN	1639644	A	13-07--2005
			DE	10210899	A1	18-09--2003
			WO	03077036	A1	18-09--2003
			WO	03077037	A1	18-09--2003
			EP	1483625	A1	08-12--2004
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			DE	3787035	T2	10-03-1994
			EP	0237041	A2	16-09-1987

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			US	5824455	A	20-10-1998
			US	5863706	A	26-01-1999
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			DE	69125328	T2	25-09-1997
			OP	4234722	A	24-08-1992
			JP	7111512	B	29-11-1995
			US	5052763	A	01-10-1991
